

**Списък на забелязаните цитати на трудовете
на проф. д.фз.н. Катя Желева Вутова**

- Г.Младенов, С.Сабчевски, К.Вутова, “Оценка эмиттанса и яркости пучков заряженных частиц, применяемых в технологических процессах”, Болг. Физ. Журнал, 14, (1987), 1, 97-102.

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